



JPW

PATENT  
Customer No. 22,852  
Attorney Docket No. 04329.3300

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:	)	
	)	
Takashi Sato et al.	)	Group Art Unit: 2829
	)	
Application No.: 10/814,303	)	Examiner: NGUYEN, Jimmy
	)	
Filed: April 1, 2004	)	
	)	
For: EXPOSURE METHOD,	)	Confirmation No.: 8598
EXPOSURE QUANTITY	)	
CALCULATING SYSTEM USING	)	
THE EXPOSURE METHOD AND	)	
SEMICONDUCTOR DEVICE	)	
MANUFACTURING METHOD	)	
USING THE EXPOSURE	)	
METHOD	)	

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**RESPONSE TO RESTRICTION REQUIREMENT**

In a restriction requirement mailed October 3, 2005, the period for response to which extends through November 3, 2005, the Examiner required restriction under 35 U.S.C. § 121 between Group I, claims 1-13, characterized by the Examiner as being drawn to a method and system of exposing the quantity of calculate; and Group II, claims 14-20, characterized by the Examiner as being drawn to a method of manufacturing semiconductor device. Applicants elect to prosecute Group I, claims 1-13, without traverse.

Please grant any extensions of time required to enter this response and charge any additional required fees to our deposit account 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,  
GARRETT & DUNNER, L.L.P.

*Robert E. Conner* #274132

Dated: November 2, 2005

By: *for Richard V. Burgujian*  
Richard V. Burgujian  
Reg. No. 31,744